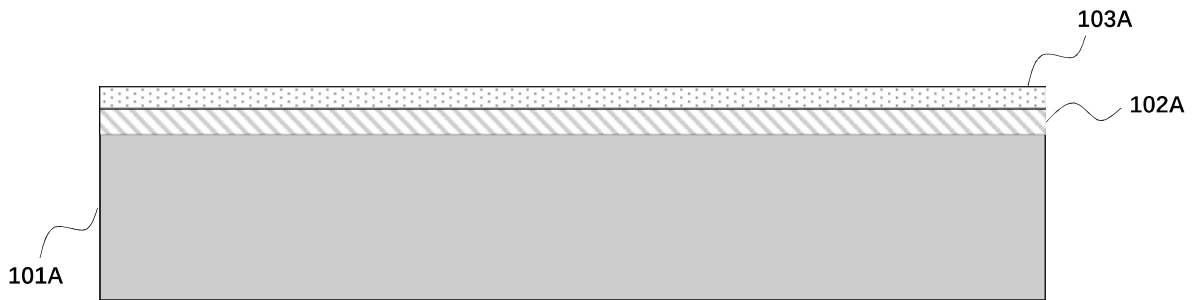




STEP 1A COATING NEGATIVE PHOTORESIST

FIG. 1A



STEP 2A COATING POSITIVE PHOTORESIST

FIG. 1B

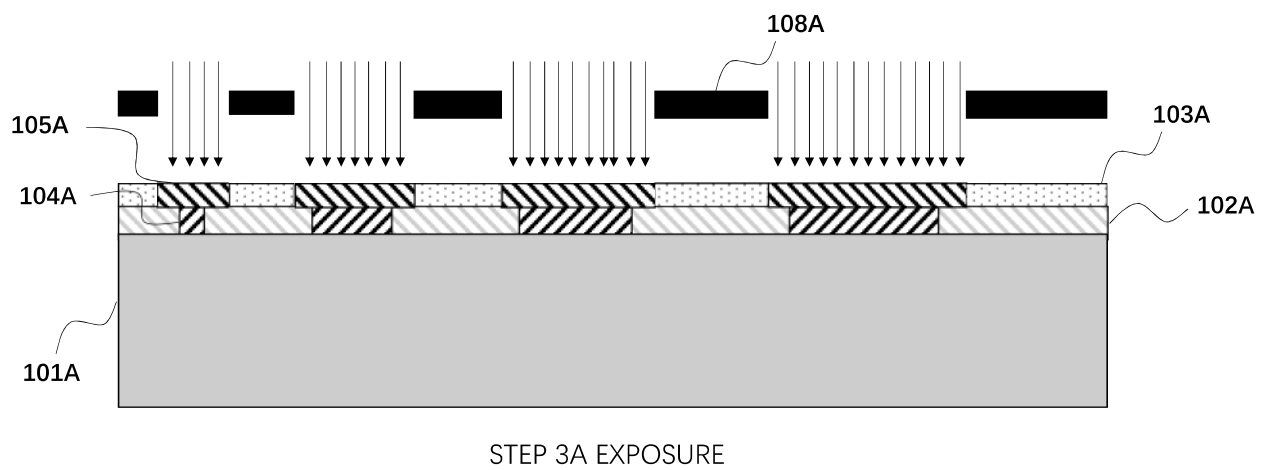
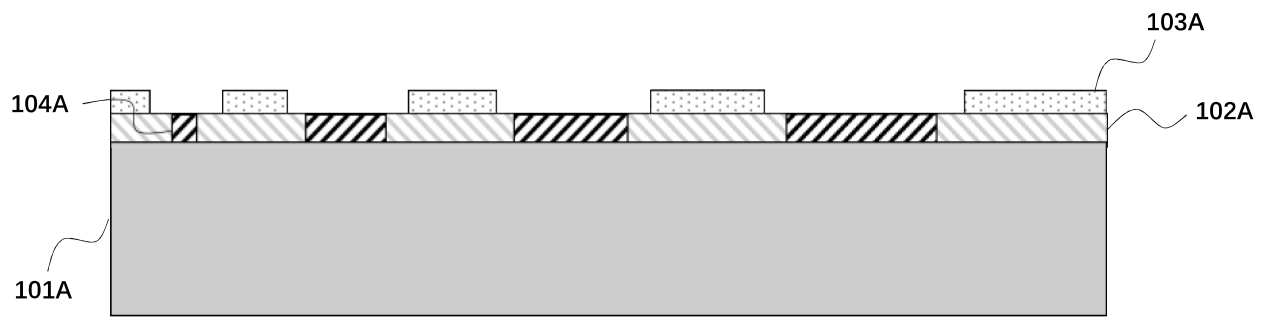
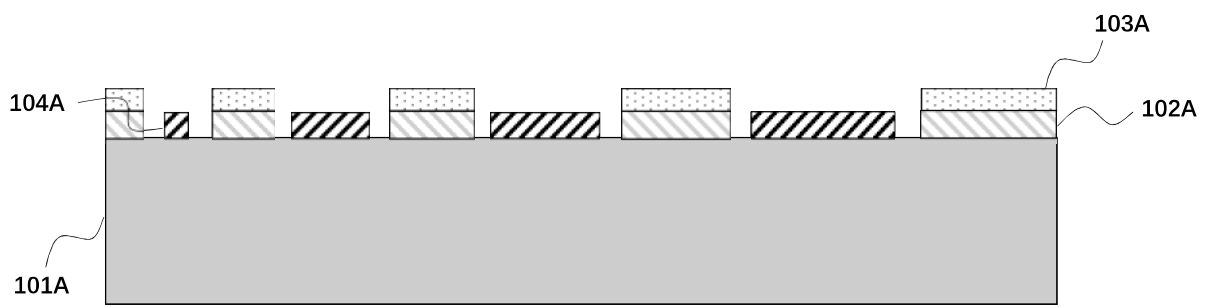


FIG. 1C



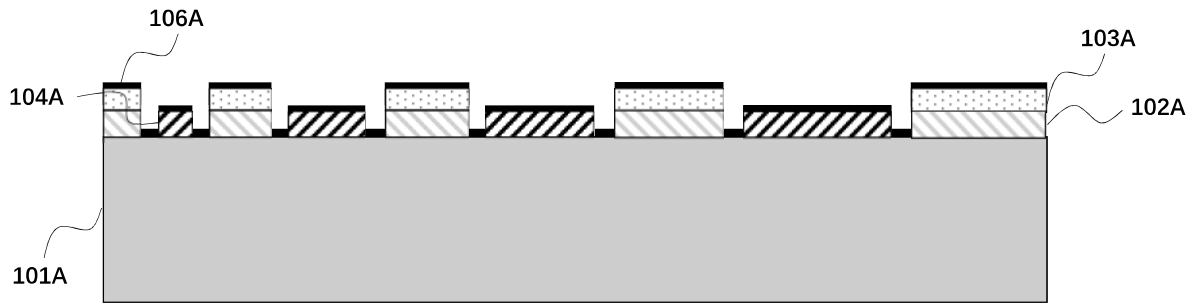
STEP 4A DEVELOPMENT FOR POSITIVE PHOTORESIST

FIG. 1D



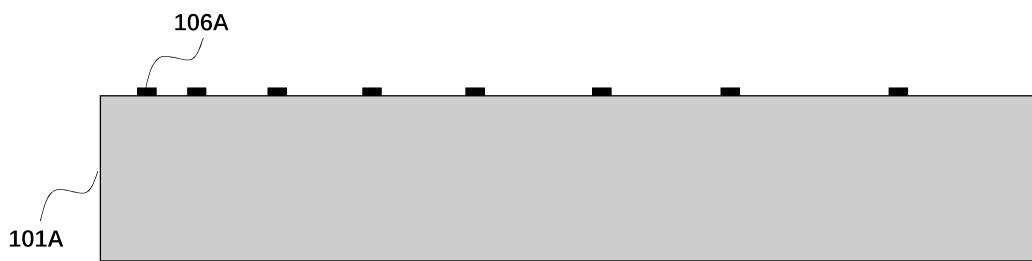
STEP 5A DEVELOPMENT FOR NEGATIVE PHOTORESIST

FIG. 1E



STEP 6A DEPOSITION

FIG. 1F



STEP 7A REMOVING PHOTORESIST

FIG. 1G

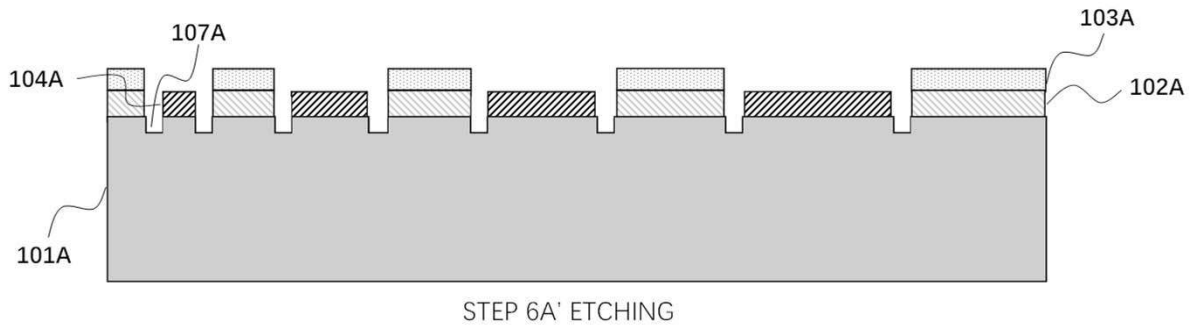


FIG. 1F'

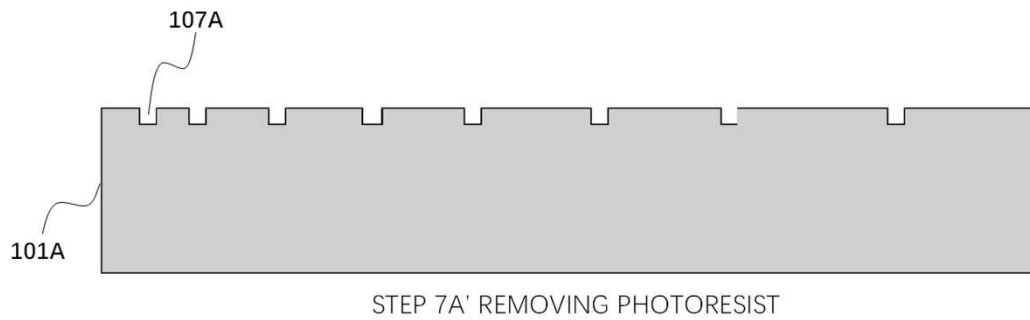


FIG. 1G'

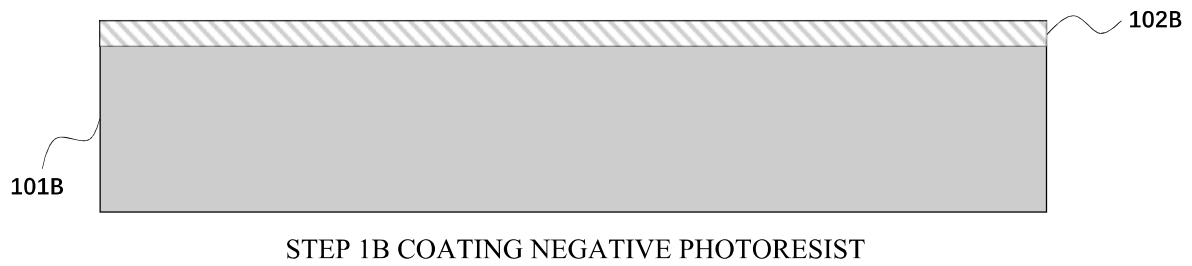


FIG. 2A

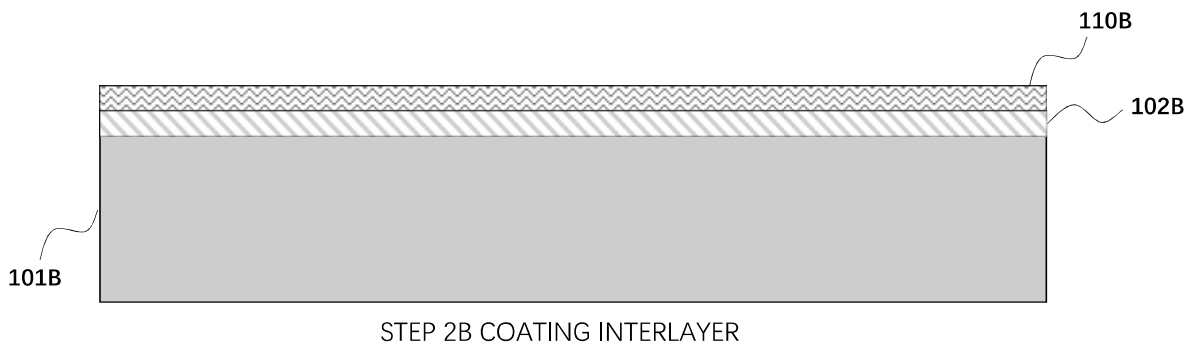


FIG. 2B

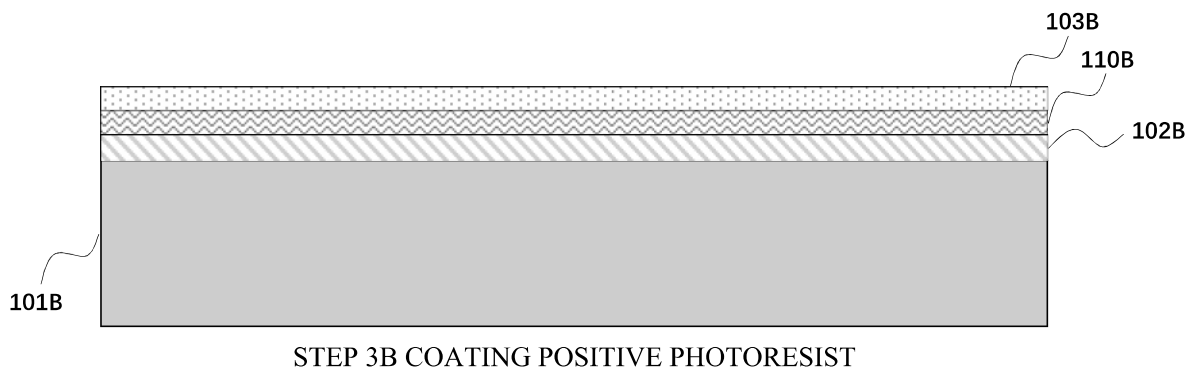
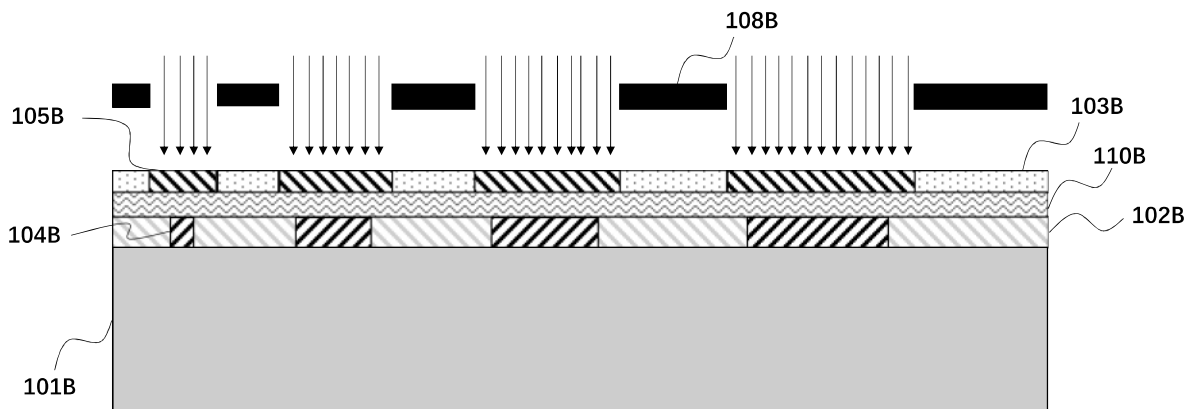
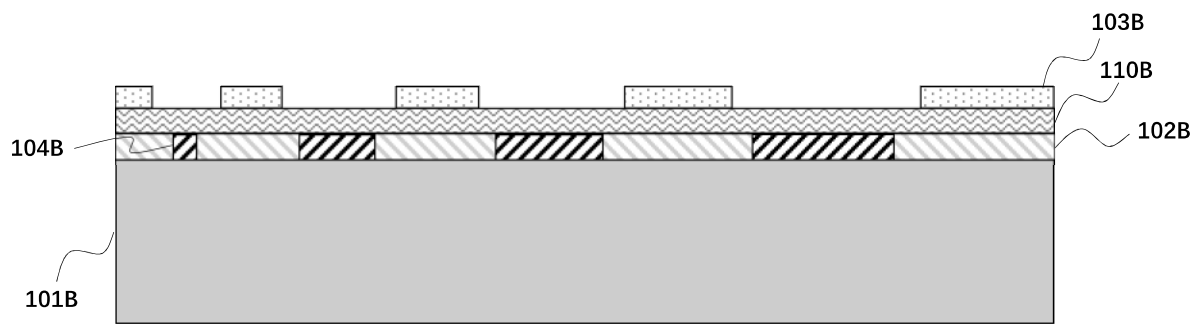


FIG. 2C



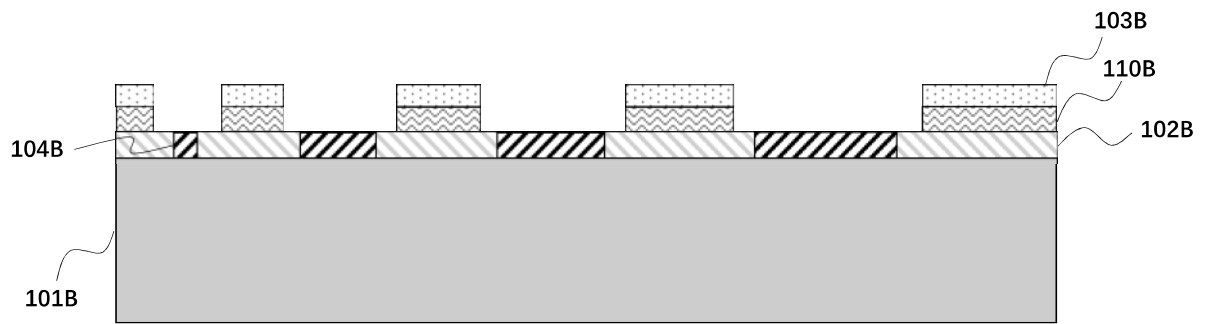
STEP 4B EXPOSURE

FIG. 2D



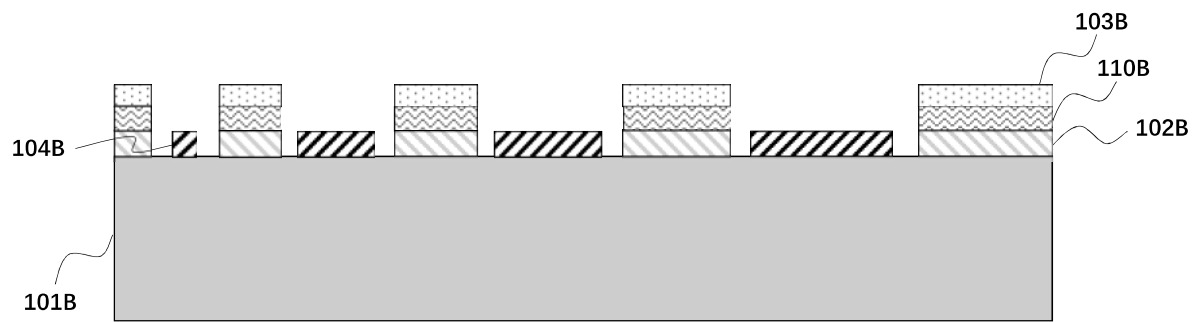
STEP 5B DEVELOPMENT FOR POSITIVE PHOTORESIST

FIG. 2E



STEP 6B PATTERNING INTERLAYER

FIG. 2F



STEP 7B DEVELOPMENT OF NEGATIVE PHOTORESIST

FIG. 2G

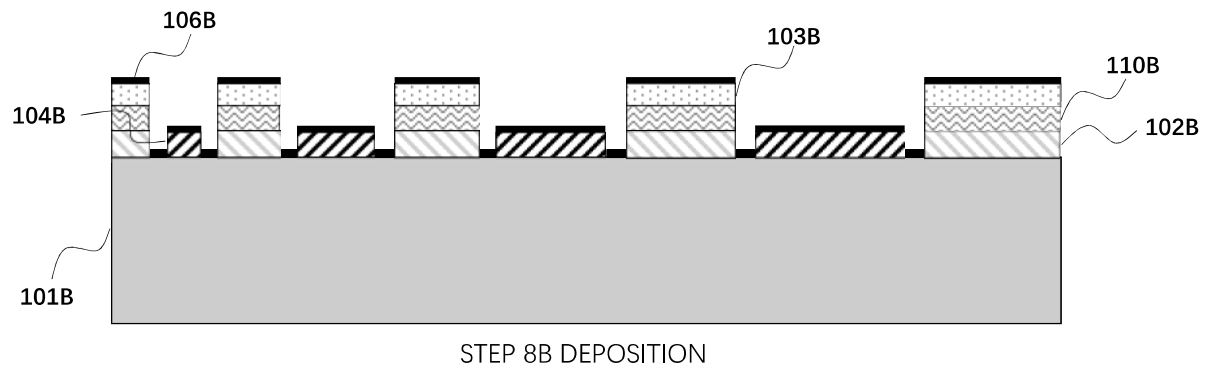


FIG. 2H

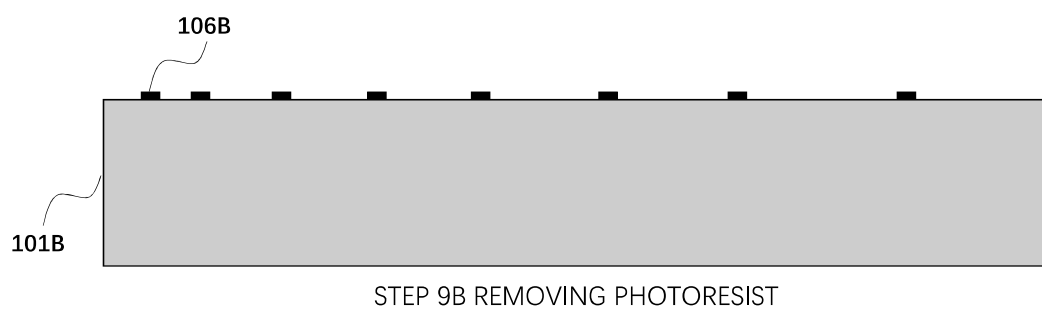


FIG. 2I

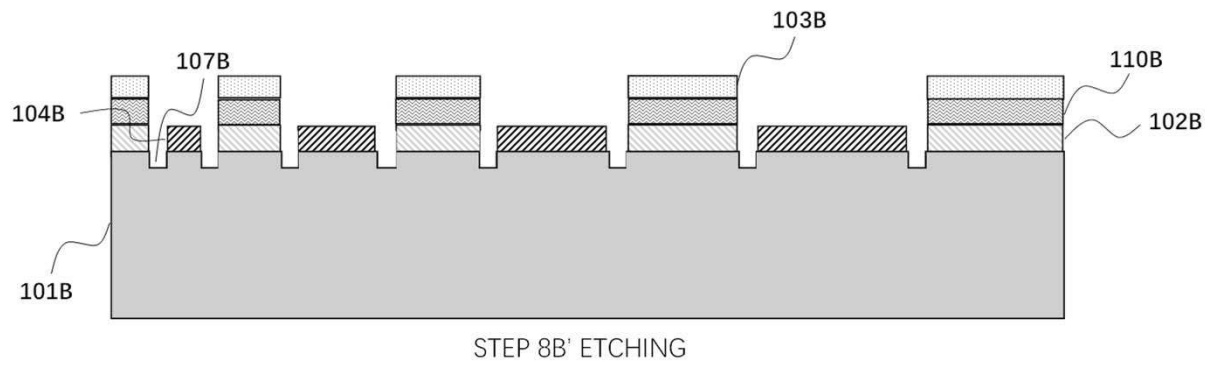


FIG. 2H'

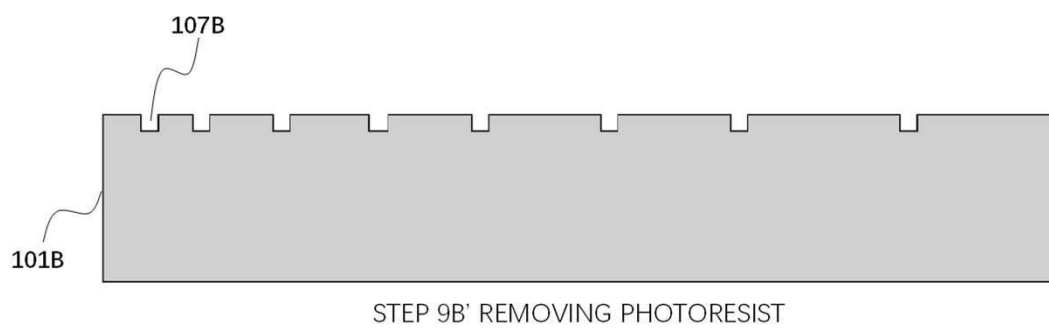


FIG. 2I'

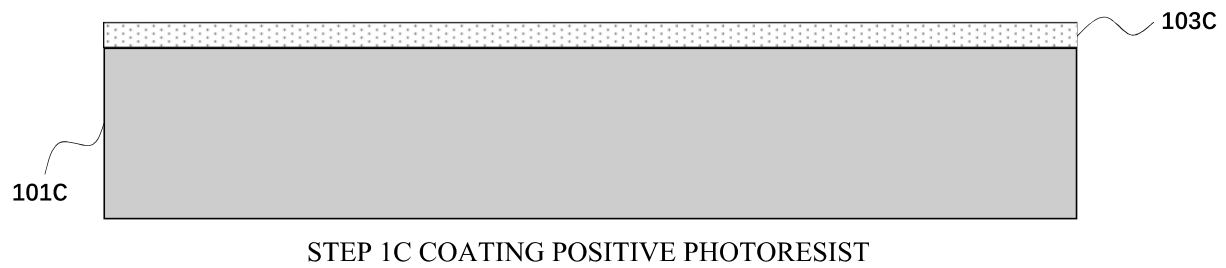


FIG. 3A

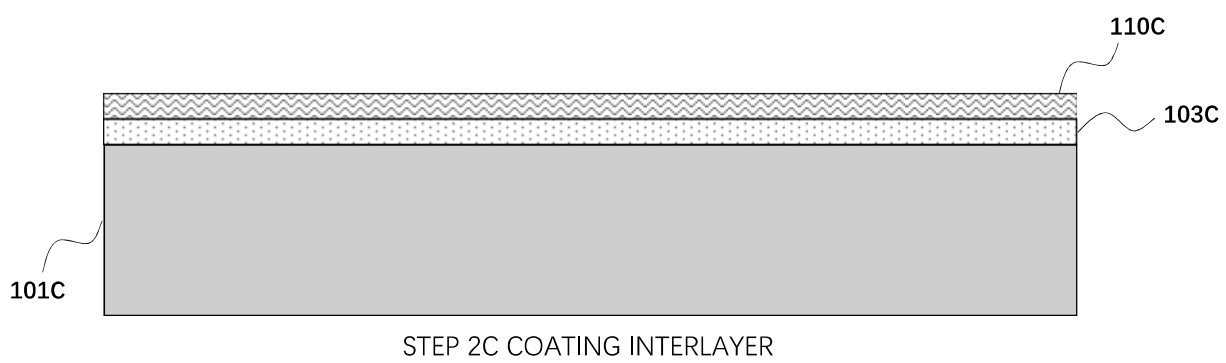
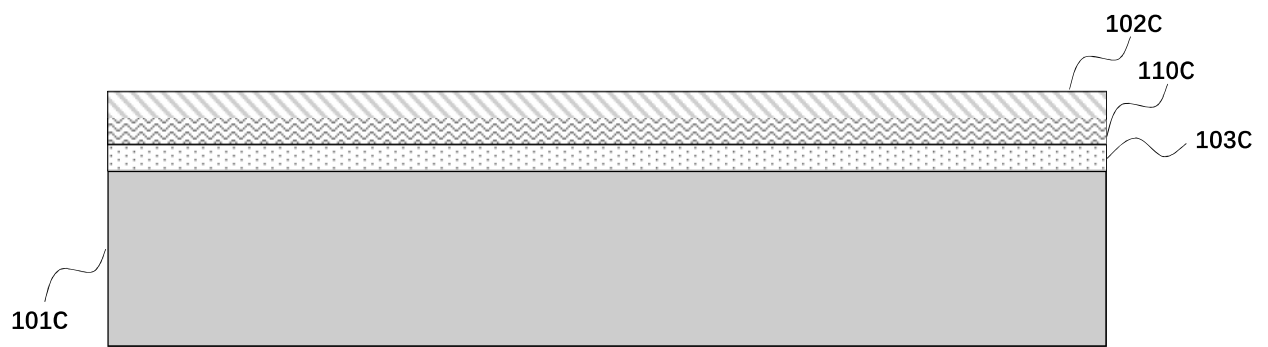
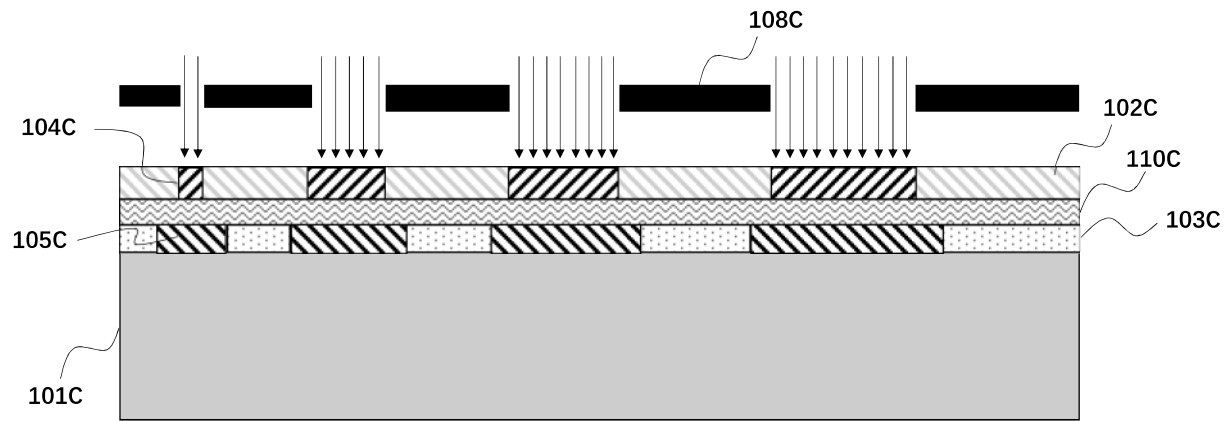


FIG. 3B



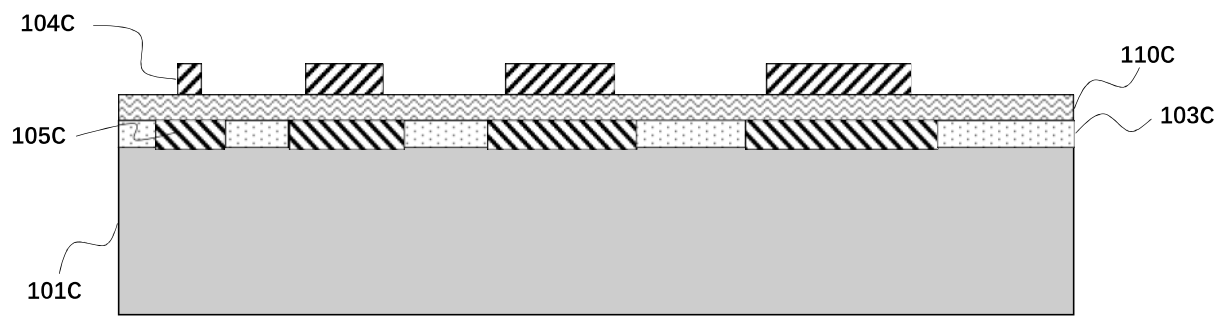
STEP 3C COATING NEGATIVE PHOTORESIST

FIG. 3C



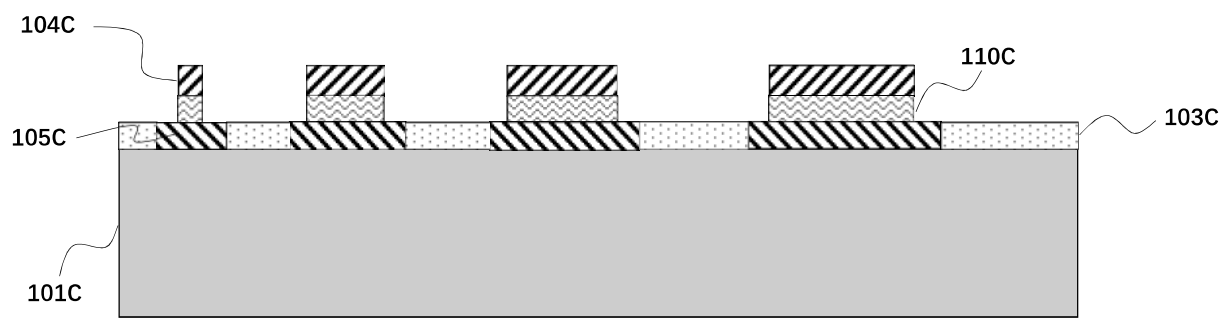
STEP 4C EXPOSURE

FIG. 3D



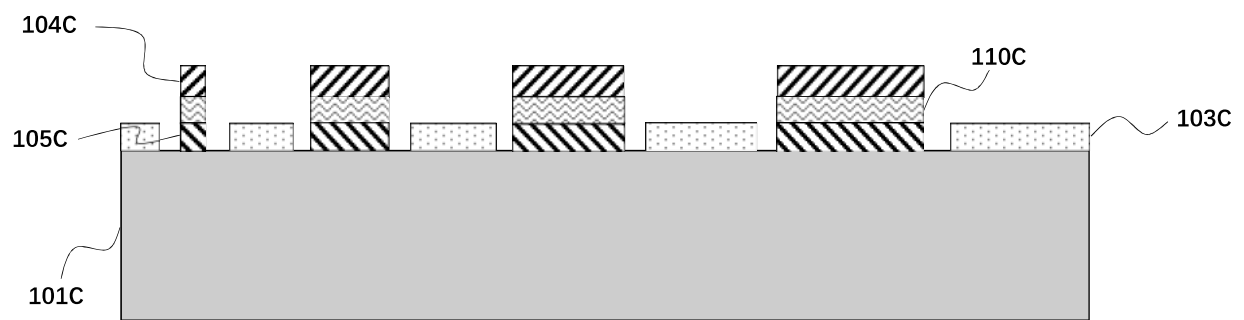
STEP 5C DEVELOPMENT FOR NEGATIVE PHOTORESIST

FIG. 3E



STEP 6C PATTERNING INTERLAYER

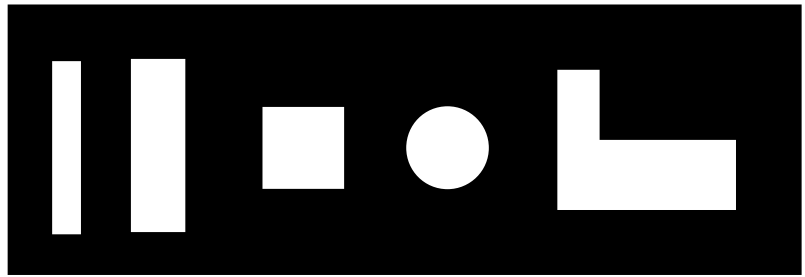
FIG. 3F



STEP 7C DEVELOPMENT FOR POSITIVE PHOTORESIST

FIG. 3G

EXPOSURE/MASK PATTERN



OBTAINED PATTERN

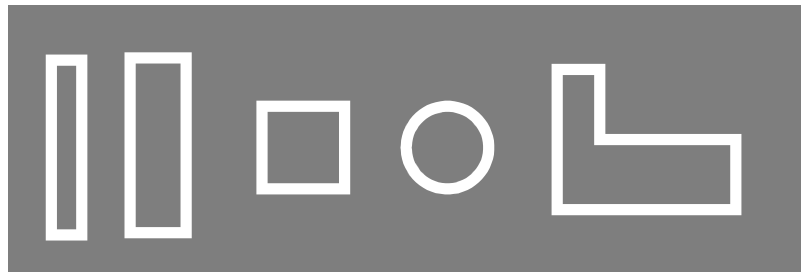


FIG. 4

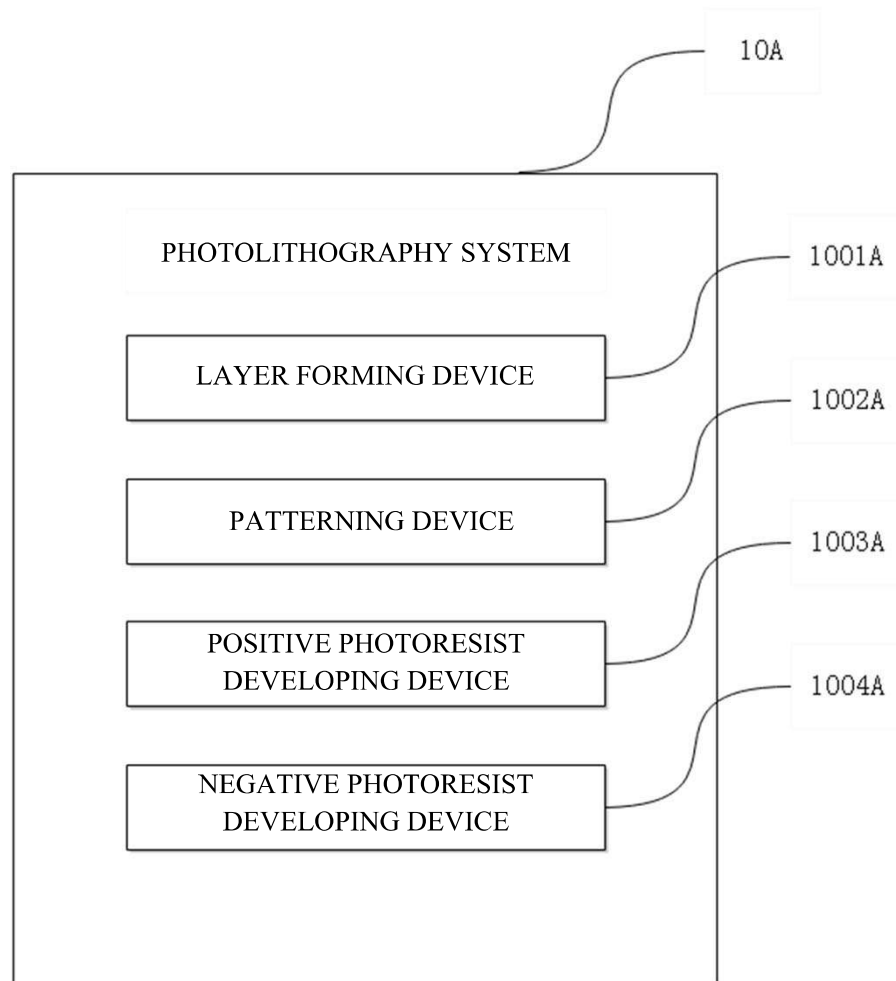


FIG. 5

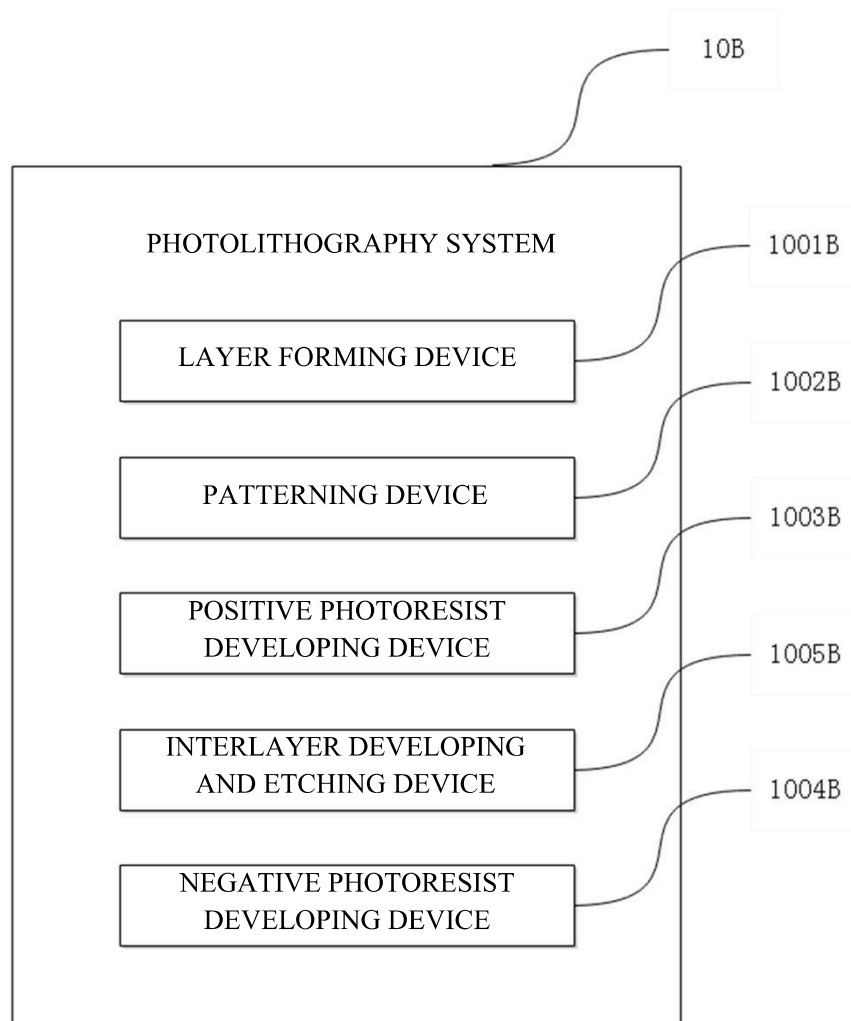
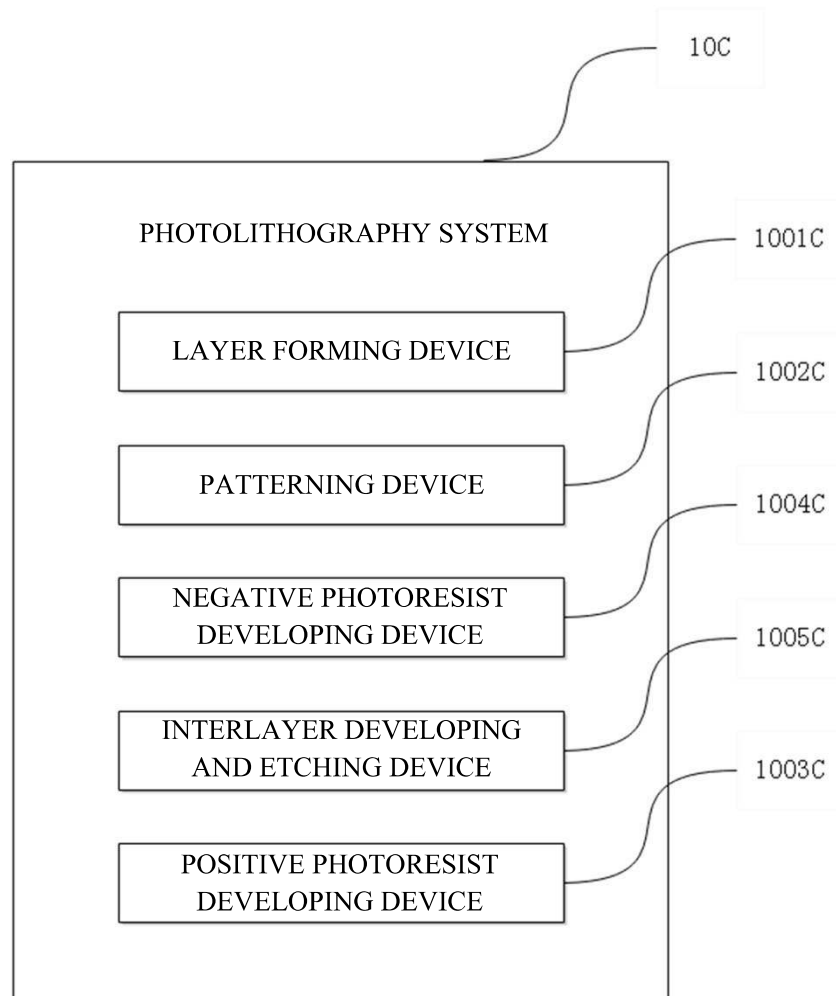


FIG. 6

**FIG. 7**